

ABSTRACT OF THE DISCLOSURE

A hole injecting electrode composed of ITO is formed on a glass substrate. On the hole injecting electrode, a hole
5 injecting layer composed of CuPc(copper phthalocyanine), a plasma thin film of CF_x formed by plasma CVD, a hole transporting layer of NPB, and a light emitting layer are formed in the order. On the light emitting layer, an electron transporting layer is formed, and an electron injecting electrode is formed
10 thereon.